



PATENT

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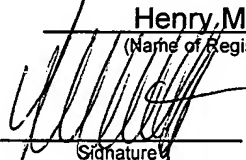
IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Docket No.: WOLFF-4

In re Application of:)
THOMAS WOLFF)
Appl. No.: 10/693,771) Examiner: Chen, Eric Brice
Filed: October 24, 2003) Group Art Unit: 1765
For: METHOD AND DEVICE FOR PHOTO-ELECTRONICALLY ETCHING A SEMICONDUCTOR SAMPLE, ESPECIALLY GALLIUM NITRIDE)

SECOND INFORMATION DISCLOSURE STATEMENT

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

I hereby certify that this correspondence is being deposited with the United States Postal Service with sufficient postage as first class mail in an envelope addressed to "Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450", on <u>June 22, 2005</u> .	
(Date)	
<u>Henry M. Feiereisen</u>	
(Name of Registered Representative)	
	<u>6-22-2005</u>
Signature	Date of Signature

SIR:

In accordance with 37 C.F.R. 1.56, applicant wishes to call the attention of the Examiner to the following references A) to B). Applicant does not admit that any of the cited documents constitutes prior art against the pending application.

	Country:	Patent or Appl. No:	Patentee or Applicant:	Issue or Filing Date:
A)	Germany	DE 195 10 852 A1	Hahn-Meitner	09-21-1995
B)	Germany	DE 41 26 916 A1	Siemens AG	02-18-1993

Copies of these references are submitted herewith along with form PTO-1449. The Examiner is requested to initial the attached form PTO-1449 and to return a copy of the initialed document to the undersigned as an indication that the attached references have been considered and made of record.

- ☐ This Information Disclosure Statement is filed within three months of the filing date of a national application other than a continued prosecution application under 1.53(d), so that no fee under 37 C.F.R. §1.97 is due.
- ☐ This Information Disclosure Statement is filed within three months of the date of entry of the national stage as set forth in 1.491 in an international application, so that no fee under 37 C.F.R. §1.97 is due.
- ☒ This Information Disclosure Statement is filed before the mailing of a first Office Action on the merits, so that no fee under 37 C.F.R. §1.97 is due.
- ☐ This Information Disclosure Statement is filed before the mailing of a first Office Action after the filing of a request for continued examination under §1.114, so that no fee under 37 C.F.R. §1.97 is due.
- ☐ This Information Disclosure Statement is filed after the issuance of a first office but before issuance of a final action under §1.113, or a notice of allowance under §1.311.
- ☐ This Information Disclosure Statement is submitted after the mailing of a final action or a notice of allowance, but before payment of the issue fee.
- ☐ The undersigned submits the following statement requesting consideration of this statement:
The undersigned hereby states:
 - ☐ That each item of information contained in the information disclosure statement was first cited in any communication from a foreign patent office in a counterpart foreign application not more than three months prior to the filing of the information disclosure statement;
 - ☐ That no item of information contained in the information disclosure statement was cited in a communication from a foreign patent office in a counterpart foreign application, and, to the knowledge of the person signing the statement

after making reasonable inquiry, no item of information contained in the information disclosure statement was known to any individual designated in §1.56(c) more than three months prior to the filing of the information disclosure statement.

- ☐ The fee of \$180.00 set forth in 1.17(p).
- ☐ The Commissioner is hereby authorized to charge the fee as set forth in 1.17(p), and any additional fees which may be required, or credit any overpayment to Deposit Account No. 06-0502.
- ☒ The Commissioner is hereby authorized to charge any fees which may be required, or credit any overpayment to Deposit Account No. 06-0502.

In addition, applicant notes with respect to any information that is not in English language as follows:

Reference A) describes a process of treating surfaces of flat Si bodies, whereby the process includes (a) pretreating the Si bodies; (b1) electrolytically polishing the surfaces in an F-contg. electrolyte soln. by anodic oxidn. and electrochemically etching; (b2) electro-analytically monitoring the polishing using a current measurer-between the Si body, present as working electrode of anodic potential, and in contact with the electrolyte soln. and a counter electrode immersed in the electrolyte soln., w.r.t. occurrence of periodic oscillation of the measured current; and (b3) registering the periodicity of oscillation over a period of time.

Reference B) describes a process of structuring the surface of an n-doped Si-substrate, whereby the process includes: (a) contacting the surface with an F-contg. acidic electrolyte (3); (b) using light source of wavelength less than 1100 NM to produce an illuminated sample (8) on the surface; (c) applying a potential between the electrolyte (3) and the Si-substrate (1) so that, on illuminated sites, an anodic minority charge carrier stream flows over the substrate effecting etching; and (d) producing the sample (8) of illuminating strength that the local current density reaches a value on no site, above which electropolishing of the surface occurs.

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The above-identified application discloses and claims an invention patentable over this prior art.

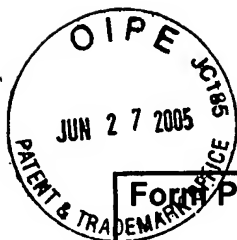
Entry of the references above set forth into the file of the above application is believed to be in order and is respectfully requested.

Respectfully submitted

By: 

Henry M. Feiereisen
Agent for Applicant
Reg. No. 31,084

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Form PTO-1449

U.S. Department of Commerce
Patent and Trademark Office

INFORMATION DISCLOSURE CITATION

Attorney's Docket No. WOLFF-4	Applicant THOMAS WOLFF	Appl. No. 10/693,771
Filing Date October 24, 2003	Group 1765	Examiner Chen, Eric Brice

U.S. PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date, if appropriate

FOREIGN PATENT DOCUMENTS

	Document Number	Date	Country	Class	Subclass	Translation
	DE 195 10 852 A1	09-21-1995	Germany			no
	DE 41 26 916 A1	02-18-1993	Germany			no

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

Examiner:

Date considered:

*Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.